

## **REMARKS**

Claims 5, 6, 11, 14, 16 and 20 are cancelled; claims 10 and 18 are amended; and claims 1-4, 7-10, 12, 13, 15, 17-19 and 21-23 are pending in the application.

The specification is amended to correct a minor typographical error.

Claims 1-3 stand rejected as being anticipated by Pradeep (U.S. Patent No. 5,866,448). Applicant requests reconsideration of such rejections.

Referring first to claim 1, from which claims 2 and 3 depend, such recites that a block consisting of photoresist and a single material other than photoresist is utilized to transfer a pattern to a conductive material. In contrast, Pradeep shows a block in Fig. 3 containing silicon oxide 40 and polymer 44 in addition to photoresist 42 (with such block being utilized for subsequent patterning a conductive material 26 at the processing stage of Fig. 4). The Examiner contends that the block of Fig. 3 anticipates the claim 1 recited block consisting of photoresist and a single material other than photoresist. Applicant respectfully submits that the Examiner is mistaken, since the block of Pradeep's Fig. 3 comprises two materials in addition to photoresist (specifically, the silicon oxide 40 and the polymer 44), and thus cannot be interpreted to consist of photoresist and a single other material. For at least this reason, claim 1 is not anticipated by Pradeep. Applicant further notes that claim 1 is not rendered obvious by Pradeep contains no suggestion that the shown block of Fig. 3 containing photoresist and two other materials can be replaced with a block consisting of photoresist and a single other material. Accordingly, claim 1 is allowable over Pradeep.

Claims 2 and 3 are allowable over Pradeep for at least the reason that such claims depend from claim 1.

Claims 12-13 and 17 are rejected as being unpatentable over Pradeep. Applicant requests reconsideration over such rejections.

Referring to claim 12, from which claims 13 and 17 depend, such claim, like the above-discussed claim 1, recites a method in which a block consisting of photoresist and a single material other than photoresist is utilized to transfer a pattern to a conductive material. Claim 12 is therefore allowable over Pradeep for reasons similar to those discussed above regarding claim 1.

Since claims 13 and 17 depend from claim 12, such claims are allowable over Pradeep for at least the reason discussed above regarding claim 12.

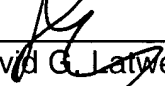
Claims 4 and 15 stand rejected as being unpatentable over Pradeep in view of Wolf. Applicant notes that claims 4 and 15 depend from claims 1 and 12, respectively, and accordingly submits that claims 4 and 15 are allowable for reasons similar to those discussed above regarding claims 1 and 12. Notably, the cited reference of Wolf does not cure the above-discussed failure of Pradeep to show or suggest the recited blocks consisting of photoresist and a single material. Accordingly, claims 4 and 15 are believed allowable over the cited references.

Claims 1-4, 7-10, 12, 13, 15, 17-19 and 21-23 stand rejected for obviousness-type double patenting relative to claims 1-13 of U.S. Patent 6,627,524. Submitted herewith is a Terminal Disclaimer which overcomes such obviousness-type double patenting rejection.

Claims 1-4, 7-10, 12-13, 15, 17-19 and 21-23 are believed to now be in condition for formal allowance, and Applicant therefore respectfully requests that the Examiner's next action be a Notice of Allowance formally allowing all of the pending claims.

Respectfully submitted,

Dated: June 7, 2005

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*Enclosure: Terminal Disclaimer*